mikron
Research Institute Of Precision
Machine Manufacturing

НИИТМ
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of Precision Machine
Manufacturing»

4-POSITION VACUUM PLANT FOR FILM DEPOSITION BY ELECTRON-BEAM EVAPORATION WITH LOCK LOAD

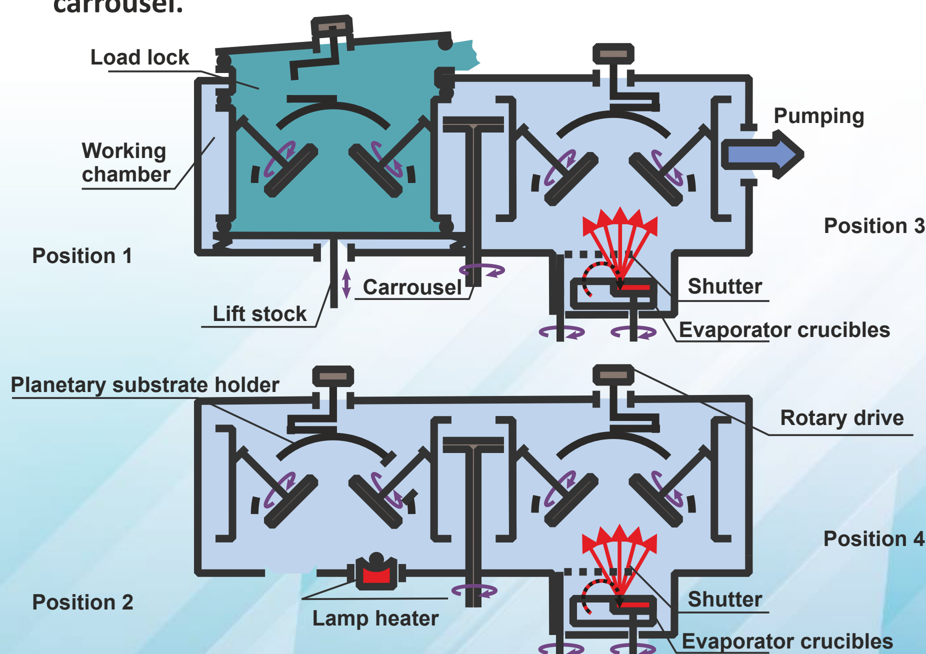
ELU TM 5

Purpose:

Deposition of thin films onto substrates (plates) by electron-beam evaporation

Special characteristics:

- Group processing of substrates in one technological cycle: Ø 76 mm – 15 pcs.; Ø 100 mm – 9 pcs.; Ø 150 mm – 3 pcs.;
- Lock-chamber for loading and unloading substrates (Position 1);
- Substrate transfer system from lock-chamber to three work positions (2, 3, 4) by transport carrousel.
- 4-crucible electron-beam evaporators;
- Preliminary substrate heating and cleaning by ion source;
- Oil-free (dry) pumping system (turbomolecular or cryogenic, forevacuum pumps);
- Microprocessing control system;
- Consumed power not more than 20 kW;
- 6 m² area per one plant.



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